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Press Release

New Products

Interference Filters for Photolithography

Photolithographic filters are used in applications with LSI and LCD steppers in which high-power mercury vapor lamps are used for illumination. The very narrow-band bandpass filters produce an almost monochromatic radiation. This allows the best possible resolution to be achieved in the target.

LASER COMPONENTS' partner Omega Optical has revised its i-line bandpass filters. The filter designs are now available based on dual magnetron reactive sputtering coating. This significantly improves both the intensity of the i-line and its homogeneity in the photolithographic process.

There is one new product from Omega that is particularly interesting for MEMS production: MicroChem, the manufacturer of the SU-8 photo resist, recommends UV radiation below 350 nm to be blocked in order to produce particularly perpendicular structures. With this in mind, the PL-360-LP from the mask aligner series can be particularly recommended!

All filters are available from LASER COMPONENTS.

More Information

<http://www.lasercomponents.com/de-en/product/photolithography-filters/>

Trade Shows

BiOS 2012, January 21-22, 2012, The Moscone Center, San Francisco, **South Hall – Booth 8517**
Photonics West 2012, Jan. 24-26, 2012, Moscone Center, San Francisco **South Hall – Booth 517**
Analytica 2012, April, 17-20, 2012, Munich International Trade Fairs, **Booth A2.400A**

The Company

LASER COMPONENTS is specialized in the development, manufacture, and sale of components and services for the laser and opto-electronics industries. With sales offices in four different countries, the company has served its customers since 1982. In-house production at six locations in Germany, Canada, and the USA began in 1986 and is meanwhile responsible for about half of its turnover. Currently, the family-run business employs more than 130 people worldwide.